

## A THREE-STEP CHAMBER CLEANING PROCESS FOR DEPOSITION TOOLS

### ABSTRACT OF THE DISCLOSURE

The present invention provides, in one embodiment, a process (100) for cleaning a deposition chamber having multiple substrate stations contained therein. The process (100) includes a first cleaning step (110) that comprises maintaining the deposition chamber at a first pressure while passing a fluorocarbon gas into the deposition chamber. The first cleaning step (100) is conducted until an endpoint is reached. The process also includes a second cleaning step (120) that comprises maintaining the deposition chamber at a second pressure while passing the fluorocarbon gas into the deposition chamber. The process further includes a third cleaning step (130) that comprises maintaining the deposition chamber at a third pressure less than the first and second pressures while passing the fluorocarbon gas into the deposition chamber.